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# Installation, calibration, and experimental verification of a layered deposition scheme



Julian Calder,<sup>1,2</sup> Rebecca Smaha,<sup>2</sup> Davi Febba,<sup>2</sup> Sage Bauers,<sup>2</sup> Dennice Roberts,<sup>2</sup> Andriy Zakutayev <sup>2</sup> <sup>1</sup> Middlebury College, <sup>2</sup> National Renewable Energy Laboratory

## Introduction and Motivation

- Layered material deposition allows for the synthesis of previously undiscovered materials
- Depositing materials in amorphous layers at ambient temperature has been shown to facilitate reordering under annealing conditions
- Prior research in chalcogenides (SnS and TaS<sub>2</sub>) at NREL <sup>1,2</sup>
  - Our goal is to expand this research to new materials, particularly nitrides <sup>3</sup>
- Exploring the viability of using high-vacuum magnetron sputtering to produce other novel nanoscale layered materials



Amorphous material deposition reordering into a layered pattern under anneal Figure from Ref. 2

#### **Sputtering Chamber Overview**







#### Sensor Installation

- Quartz crystal monitors (QCMs) installed above each sputtering gun, adjacent to substrate
- Water cooling lines run in parallel to each sensor to allow for high-temperature growths without compromising sensor integrity

#### **Sensor Calibration**

- Several films of Mg<sub>x</sub>N<sub>y</sub> and W<sub>x</sub>N<sub>y</sub> produced under identical growth conditions
- Thickness determined by using Dektak8 profilometer and averaging across all films

Exterior and interior of Combi 9 sputtering chamber. Note QCMs circled in blue

Film density, z-ratio, and tooling factor adjusted to ensure agreement between **QCM** thickness and measured thickness

#### Testing Layered Growths with MgWN<sub>2</sub>



Representation of sputter deposition setup with compositional gradient and substrate masking shown

modeling software <sup>4</sup>

#### Conclusions

- XRR data revealed that layering was present, though not at the desired layer thicknesses
- Future research will explore varying deposition conditions to increase likelihood of successful superstructure formation of MgWN<sub>2</sub> and other novel nitrides
- Substrate temperature (employing a liquid  $N_2$  substrate cooling system)
- **Gun power**
- Chamber pressure

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#### References

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X-ray reflectometry (XRR) data of numerous layered growths